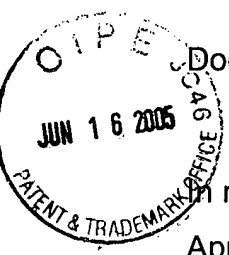


IFW



Docket No. TIP288US

TI-35995

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re **PATENT** application of:

Applicant: Udayakumar et al.

Application No.: 10/635,994

For: LOW SILICON-HYDROGEN SiN LAYER TO INHIBIT HYDROGEN
RELATED DEGRADATION IN SEMICONDUCTOR DEVICES
HAVING FERROELECTRIC COMPONENTS

Filing Date: August 7, 2003

Examiner: George Fourson

Art Unit: 2823

REPLY TO OFFICE ACTION DATED MAY 4, 2005

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Favorable reconsideration of the above-identified application is respectfully
requested in view of the following remarks.